

**INFORMATION
DISCLOSURE STATEMENT
BY APPLICANT**

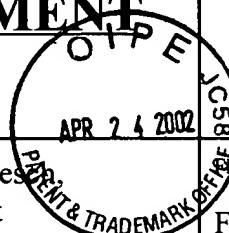
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APPLICANTS: Robert L. Gerlach, Paul P. Testa,
Lynwood W. Swanson and Mark W. Utlaut



FILING DATE

February 8, 2001

GROUP ART UNIT

2881

U.S. PATENT DOCUMENTS

*Examiner Initial	Cite No.	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if appropriate)
BES	A	3,717,785	02/20/73	Guernet	313	231	
BES	B	4,126,781	11/21/78	Siegel	250	281	
BES	C	4,390,789	06/28/83	Smith et al.	250	492.2	
BES	D	4,694,178	09/15/87	Harte	250	396 R	

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

*Examiner Initial	Cite No.	Document Number	Date	Country	Abstracts	Class	Subclass	Translation	
								Yes	No
BES	P	JP57228416	27 Dec 82	Japan	Japan	H01J37	317		
BES	Q	JP07159063	26 Jun 95	Japan	Japan	H01J37	305		
BES	R	WO9848443	29 Oct 98	WIPO		H0137	30		
BES	S	WO9934397	08 Jul 99	WIPO		H01J37	28		
BES	T	WO9947978	23 Sep 99	WIPO		H01J37	317		

OTHER DOCUMENTS
(INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

*Examiner Initial	Cite No.	Title
BES	U	NGO V.V; BARLETTA B; GOUGH R; LEE Y; LEUNG N. and ZAHIR N. "Maskless Micro-Ion-Beam Reduction Lithography", EIPBN 1999, pp 241-242.
BES	V	KIM H. S; YU M. L; THOMSON M; G. R; KRATSCHMER E. and CHANG J. "Performance of Zr/O/W Schottky Emitters at Reduced Temperature", Vac. Sci. Technol. B. 15(6), Nov/Dec 1987, pp 2284-2288.
BES	W	LEUNG K. "Plasma Sources for Electron and Ion Beams", EIPBN 1999, pp 373

EXAMINER

Bernard Souw

DATE CONSIDERED

01/13/03

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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U.S. PATENT DOCUMENTS

*Examiner Initial	Cite No.	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if appropriate)
BES	E	4,818,872	04/04/89	Parker et al.	250	309	
BES	F	5,199,917	04/06/93	MacDonald et al.	445	24	
AES	G	5,363,021	11/08/94	MacDonald	315	366	
BES	H	5,435,850	07/25/95	Rasmussen	118	726	
BES	I	5,637,539	06/10/97	Hofmann et al.	438	20	
BES	J	5,834,770	11/10/98	Holkeboer et al.	250	281	
BES	K	5,945,677	08/31/99	Leung et al.	250	396 R	
BES	L	5,981,962	11/09/99	Groves et al.	250	492.23	
BES	M	6,023,060	02/08/00	Chang et al.	250	310	
BES	N	6,218,060 B1	04/17/01	Yasuda et al.	430	30	
BES	O	6,218,664 B1	04/17/01	Krans et al.	250	310	

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								Yes	No

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